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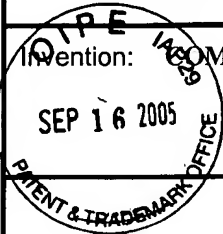
WU, Ives J.

Group Art Unit

1713

Invention: COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME

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I hereby certify that this English Language abstract of JP 5-74700 - 1 Page

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PATENT ABSTRACTS OF JAPAN

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(21)Application number : 03-250201 (71)Applicant : ASAHI GLASS CO LTD

(22)Date of filing : 04.09.1991 (72)Inventor : AOSAKI KOU

YOKOZUKA TOSHISUKE

(30)Priority

Priority number : 03202337

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Priority country : JP

(54) PATTERN FORMING METHOD

(57)Abstract:

PURPOSE: To provide a pattern forming method by which multiple interference of light which becomes an obstacle for fine patterning can be extremely reduced, the manufacturing yield can be improved, and a fine pattern can be effectively formed.

CONSTITUTION: In this pattern forming method, exposure is performed after forming a reflection preventing film on the surface of a photoresist at the time of forming a pattern by photolithography. An amorphous fluorine-bearing polymer is used for forming the reflection preventing film.

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